



Call for Papers



ISPlasma2015 / IC-PLANTS2015

7th International Symposium on
Advanced Plasma Science and its Applications for Nitrides and Nanomaterials /
8th International Conference on Plasma-Nano Technology & Science

March 26-31, 2015

Nagoya University, Japan

Organizing Committee

Chairperson : Nagahiro Saito, Nagoya University
Vice-Chairperson : Keiji Nakamura, Chubu University
Akihiro Wakahara, Toyohashi University of Technology
Noritsugu Umehara, Nagoya University

ISPlasma/IC-PLANTS is specialized international symposium where about 1,000 world-leading scientists and engineers can get together in the Tokai region (central Japan) to discuss latest researches in the fields of advanced plasma science, its application for processing and manufacturing of wide-bandgap materials and nanomaterials. This symposium will address issues such as global warming, resources and energy problems to which advanced plasma science and its application technologies can greatly contribute. We aim that holding of this symposium stimulates progress of plasma science and its application, and contributes to the improvement of social life.

Plasma Science

- Plasma Generation
- Plasma Deposition
- Etching Process
- Atmospheric-pressure plasma
- Solution Plasma
- Plasma Control
- Plasma Biology and Medicine
- Modeling and Simulation
- Plasma for Clean Energy
- Plasma for Nanotechnology

Functional Semiconductors

- Crystal Growth of GaN, SiC, Diamond, and Related Materials
- Optical Devices
- Power Devices
- Electron Devices

Nanomaterials and nano/micro fabrication

- Nano Structured Materials
- Catalyst/Battery
- Solar Cell
- Environmental Materials
- Micro-TAS

Surface Functionalization

- Hard Coating
- Thin Films by Chemical Process
- Biosurface and Biointerface
- Functional Thin Films

● ABSTRACT SUBMISSION

Online abstract submission (one-page English) will be available from September, 2014.

Deadline: October 17, 2014

● AWARD

Selected presentations will be awarded.

<http://www.isplasma.jp/>

● SPECIAL ISSUE

Selected papers will be published in a special issue of Jpn. J. Appl. Phys.(JJAP).

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